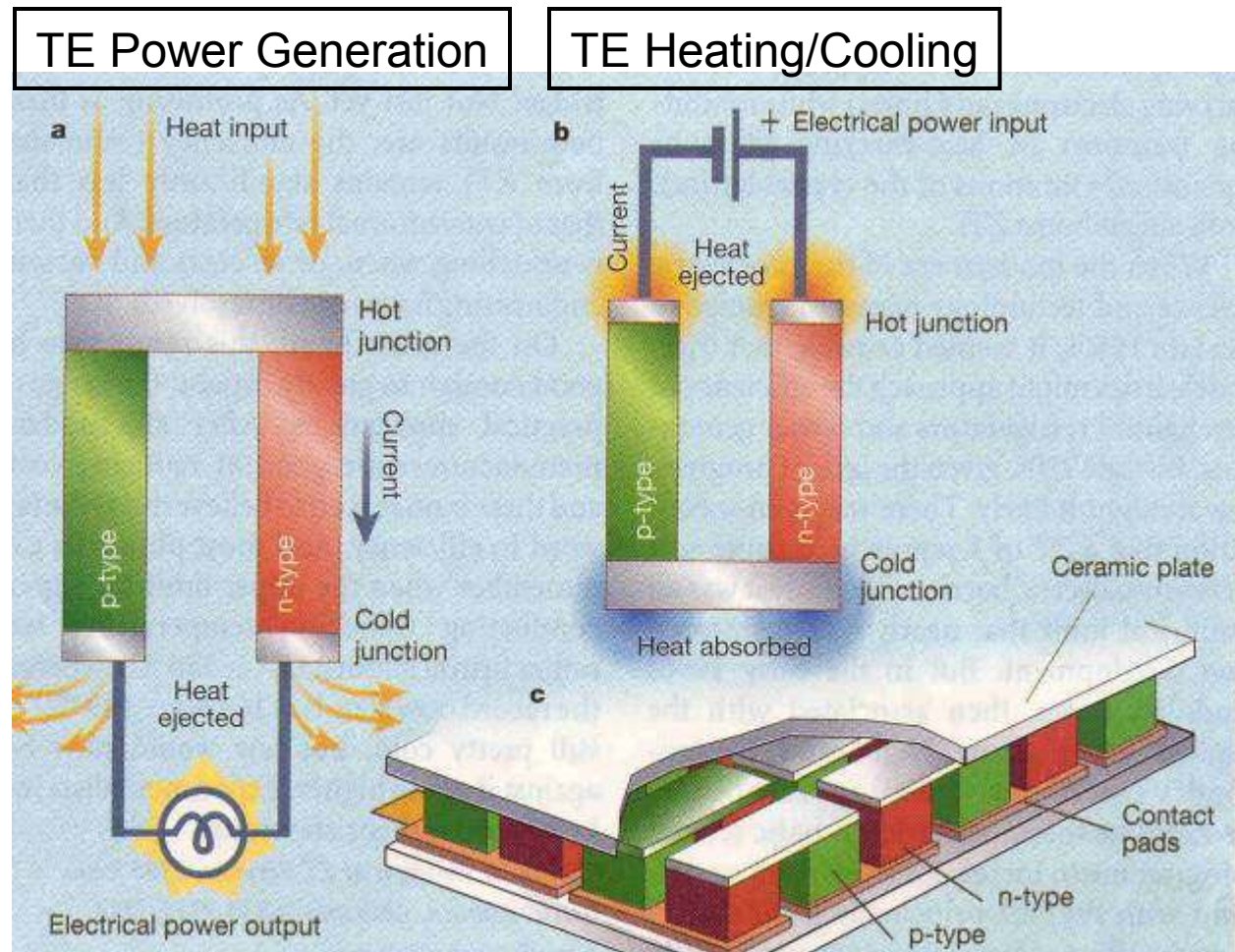


Nanostructured Multilayer Films for Advanced Detector and Thermoelectric Applications

Peter M. Martin, L. C. Olsen
Pacific Northwest National Laboratory
Richland, WA

Thermoelectric Applications

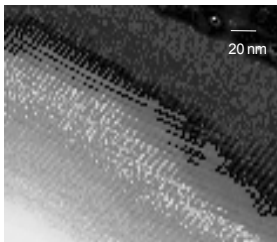
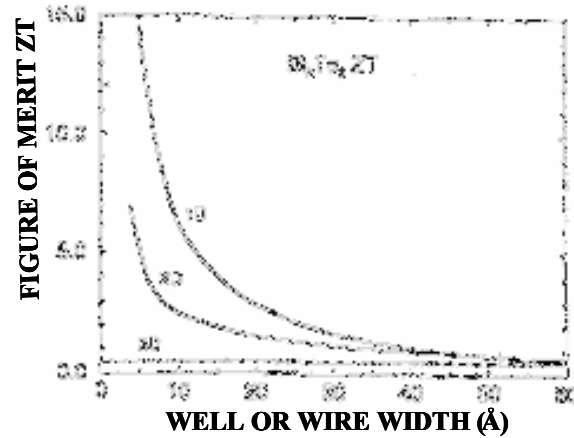
- Power Generation
 - Radioisotopes
 - Nuclear reactor systems
 - Engine Exhaust
 - Process Industries
- Thermoelectric heating/cooling for temperature/ climate control
 - Equipment, components
 - Vehicular systems
- Thermoelectric conversion efficiency **>>15% desired**



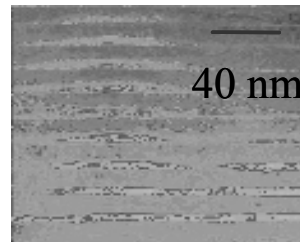
Detector Applications

- Low voltage power source
- Stand alone wireless sensory devices
- Photonic
- Neutron

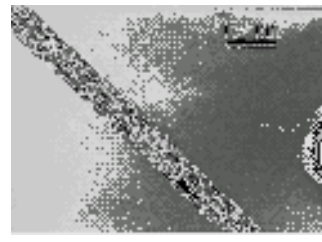
Tailored nanostructured materials could be key to high ZT and reliable performance



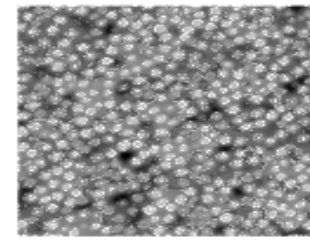
Bulk



Superlattice
2D



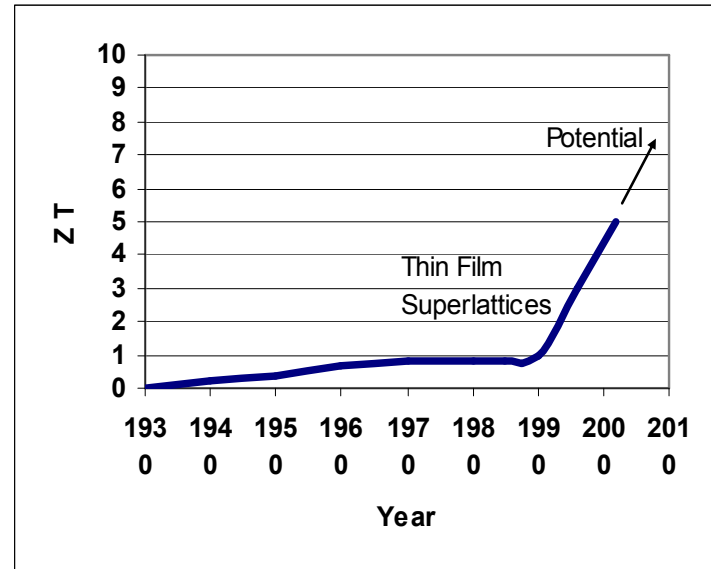
Nanowire
1D



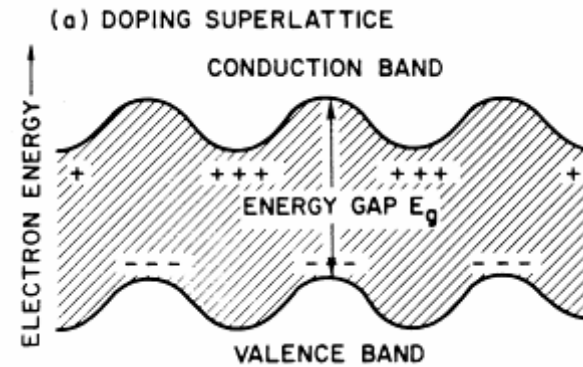
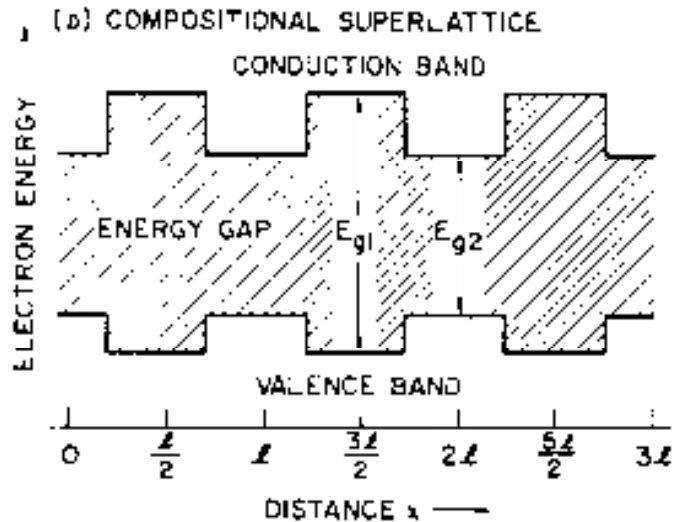
Quantum Dots
0D

Promise of Quantum Confinement in Nanostructures

- Quantum confinement increases density of states
- Increased conductivity
- Increased Seebeck coefficient
- Increased ZT
- **Increased power conversion efficiency**



TE Superlattice Concept



J. M. Chamberlain, L. Eaves, J. C. Portal, *Electronic Properties of Multilayers and Low-Dimensional Semiconductor Structures*, Plenum Press, New York, 1990.

Why thin films?

- Properties of bulk materials determined primarily by composition and microstructure
- Properties of thin films
 - Microstructure
 - Composition
 - New and more compositions possible
 - Quantum and quantum well effects
 - Nanostructures
 - Thickness
 - Band gap engineering
- Higher TE power per gram possible
- New TEG device configurations
- Higher TEG power output

Important TE Properties

- Figure of merit $ZT = \sigma S^2 T / \kappa$
- TEG efficiency derived from ZT
- Power factor = $\sigma S^2 T$ (excludes κ)
- PF between 0.01 and 0.05 desirable
 - For $\kappa \sim 0.02$ W/cmK

TE Materials/Device Development at PNNL

- Multilayer thin film TE materials developed on single crystal Si
 - Si/SiGe
 - BC (Ge)
 - Power factors of multilayer > single layer films
 - High Power factor -> $ZT > 2$ (300K)
- Process for multilayer thin film coatings scaled up to 0.5 m²
- *Development of multilayer thin film TE materials on non-Si substrates initiated*
- *Integration of thin film materials into TEG modules*
- *TEG efficiency measurements*

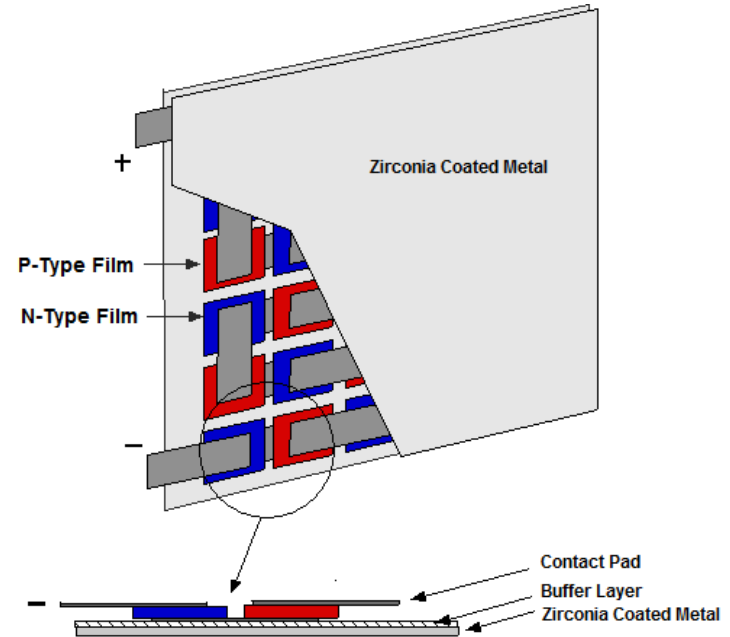
Scale up to 0.5 m² Substrate



Improved thin-film materials, low-cost scale-up, device design and packaging, and thermal management required for applications

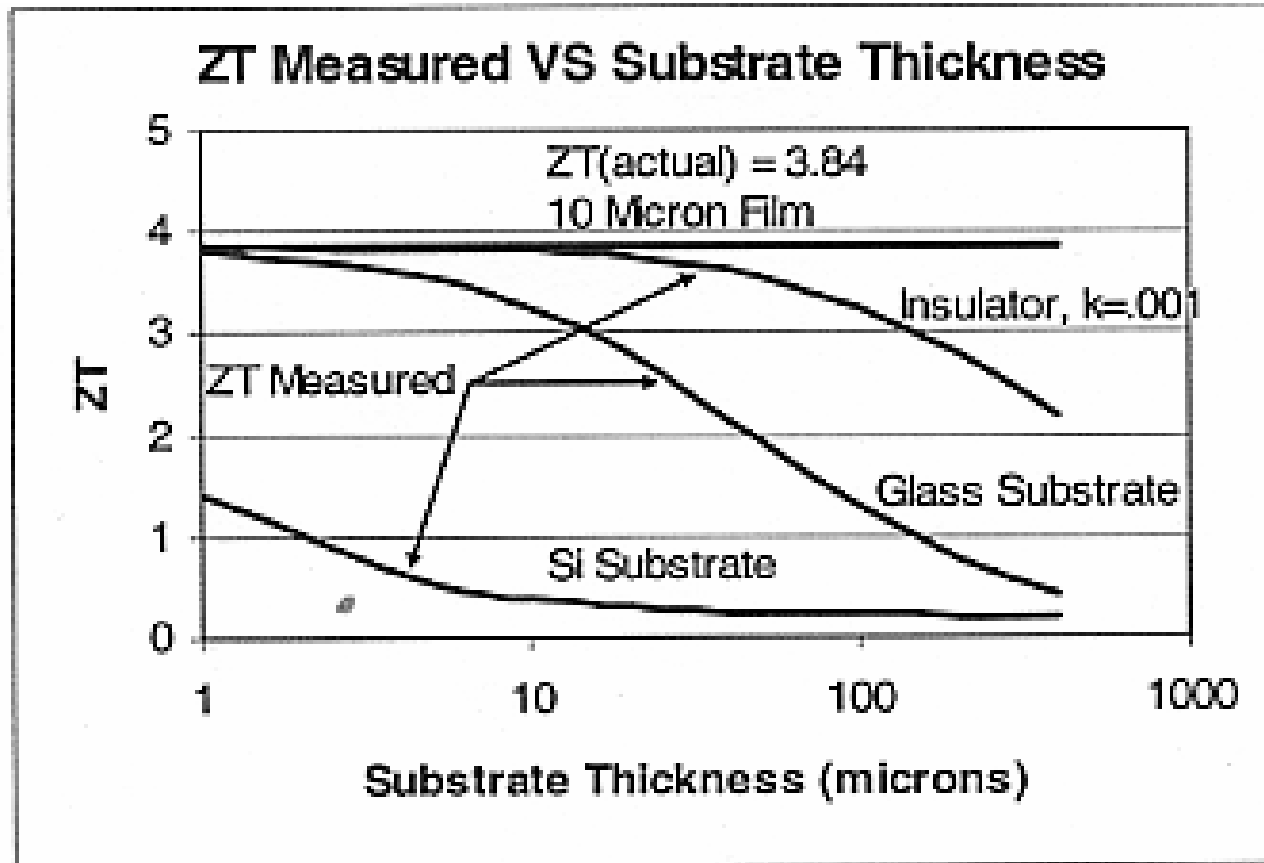


Large-Area Sputter Deposition



Device Design Schematic

Calculated Effective ZT



Bottom Line: High efficiency TEG devices cannot be realized with high ZT materials on Si substrates.

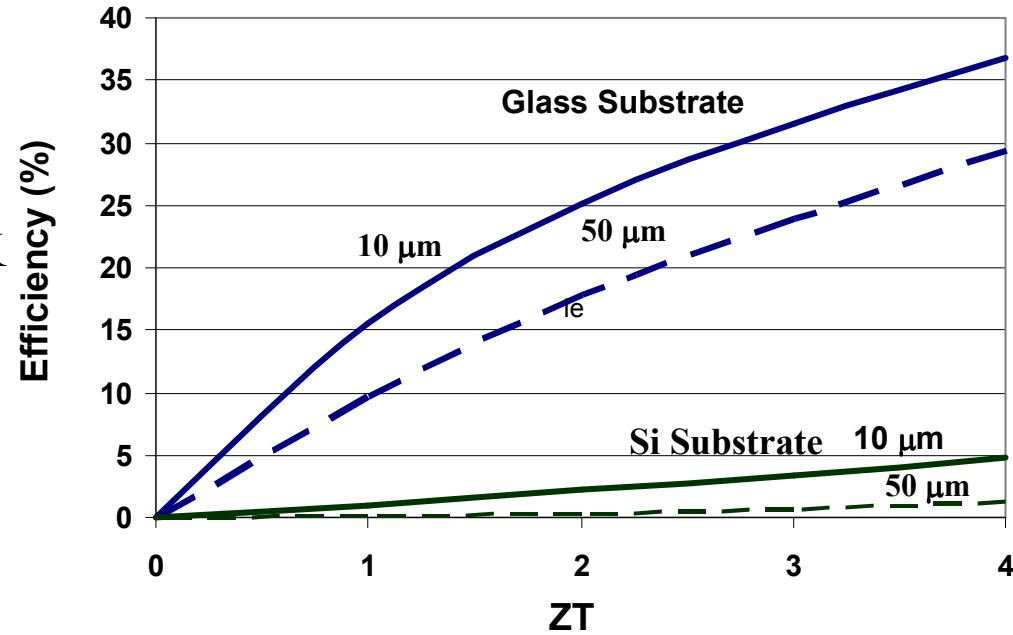
Reality check

- A lower ZT structure on a NC substrate will result in a higher TEG efficiency than a high ZT structure on a Si substrate

Effect Of Substrate For TE Thin Films

Assumptions

- 10 μm TE Film
- Z Constant from 300°K to 700 K
- ZT Calculated for $T = 300^\circ\text{K}$
- Estimated Efficiency for $\Delta T = 400^\circ\text{K}$



The Challenge

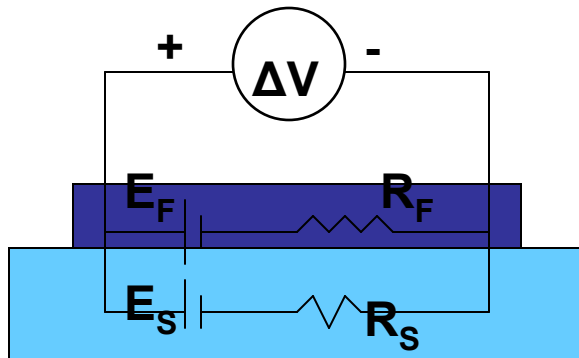
- Presently the power factor of TE films on NC substrates is an order of magnitude less than those on Si
- *Grow highly oriented crystalline thin film multilayer materials on low cost, non crystalline substrates*
 - *Large area*
 - *Low cost*
 - *Web substrates might be important*
- *Easy assembly/connection in a TE module*
 - *Not the same as bulk!*

Measurement Approach

Key Features

- ❑ Ohmic Contacts Applied to Film and Substrate
- ❑ Soldered Thermocouples
- ❑ Gold Plated Heater Assemblies

Assumed Model

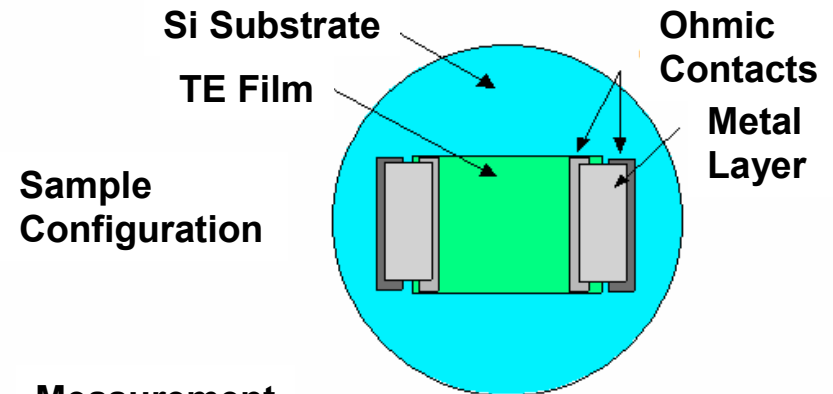


$$E_F = S_F(\Delta T)$$

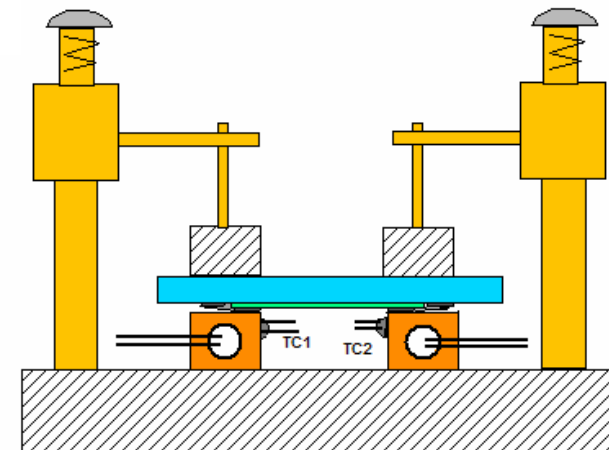
$$E_S = S_S(\Delta T)$$

$$R_{MEAS} = \frac{R_F R_S}{(R_F + R_S)}$$

$$S_{MEAS} = S_F + R_F \left(\frac{S_S - S_F}{R_S + R_F} \right)$$

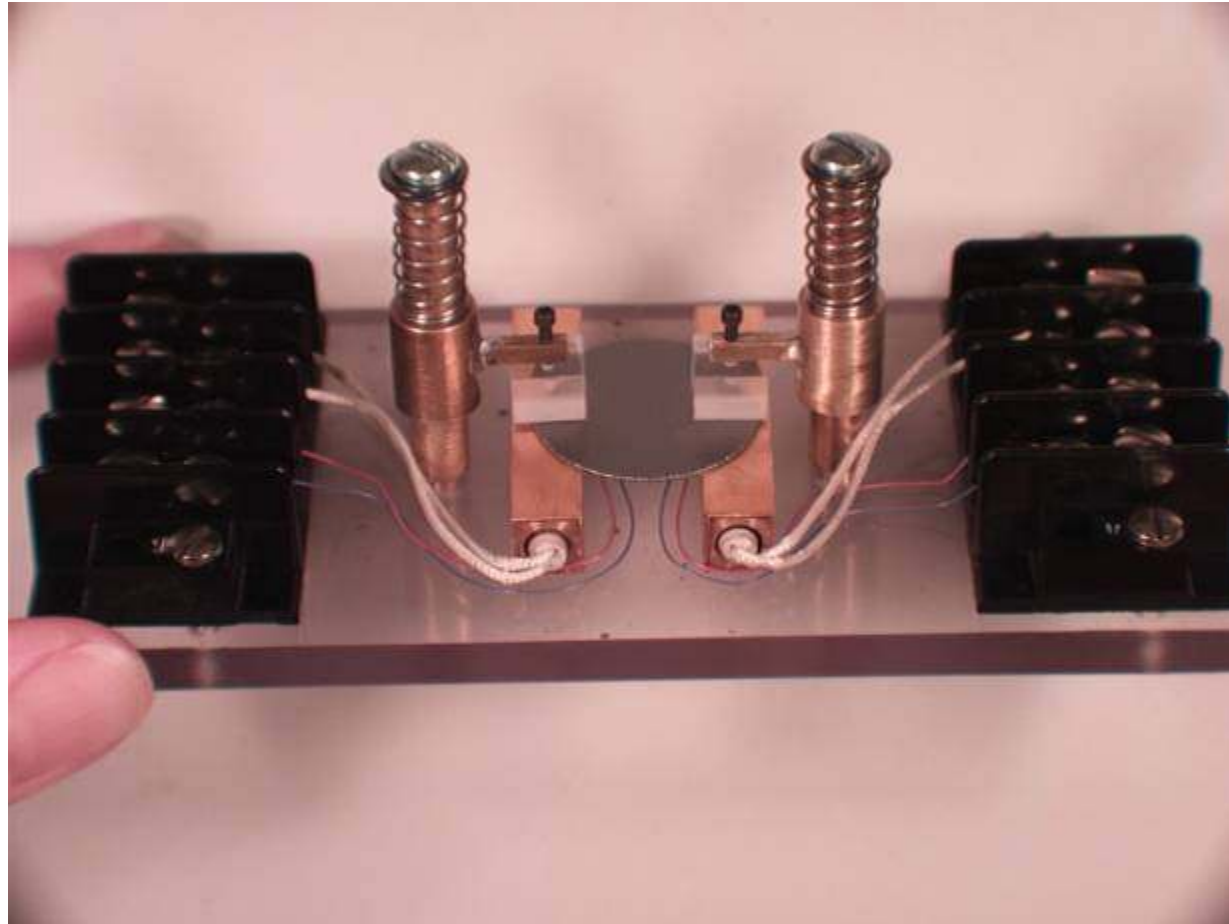


Sample Configuration



Measurement Fixture

Measurement Fixture



Thin film Si/Si_{0.8}Ge_{0.2} on Si

Material	Electrical Conductivity (ohm⁻¹cm⁻¹)	Seebeck Coefficient (μV/°C)	Power Factor
N-Silicon	60	600	0.0065
N-SiGe	35	800	0.0067
N-Si/SiGe ML	300	750	0.051

Thin film BC Results

Sample	Process	σ $(\Omega\text{-cm})^{-1}$	S ($\mu\text{V}/^\circ\text{C}$)	PF
B ₉ C-Ge	600 °C	35	340	0.0012
B ₉ C-Ge	HT @ 1000°C	1660	223	0.025
(B ₄ C/B ₉ C- Ge) ²⁰	600 °C HT@1000 °C	2560	201	0.031
(B ₄ C/B ₉ C- Ge) ¹⁰	600 °C	4160	233	0.068*
B ₉ C/ sapphire	600°C HT @ 1000 °C	118	170	0.001

New Materials: results to date

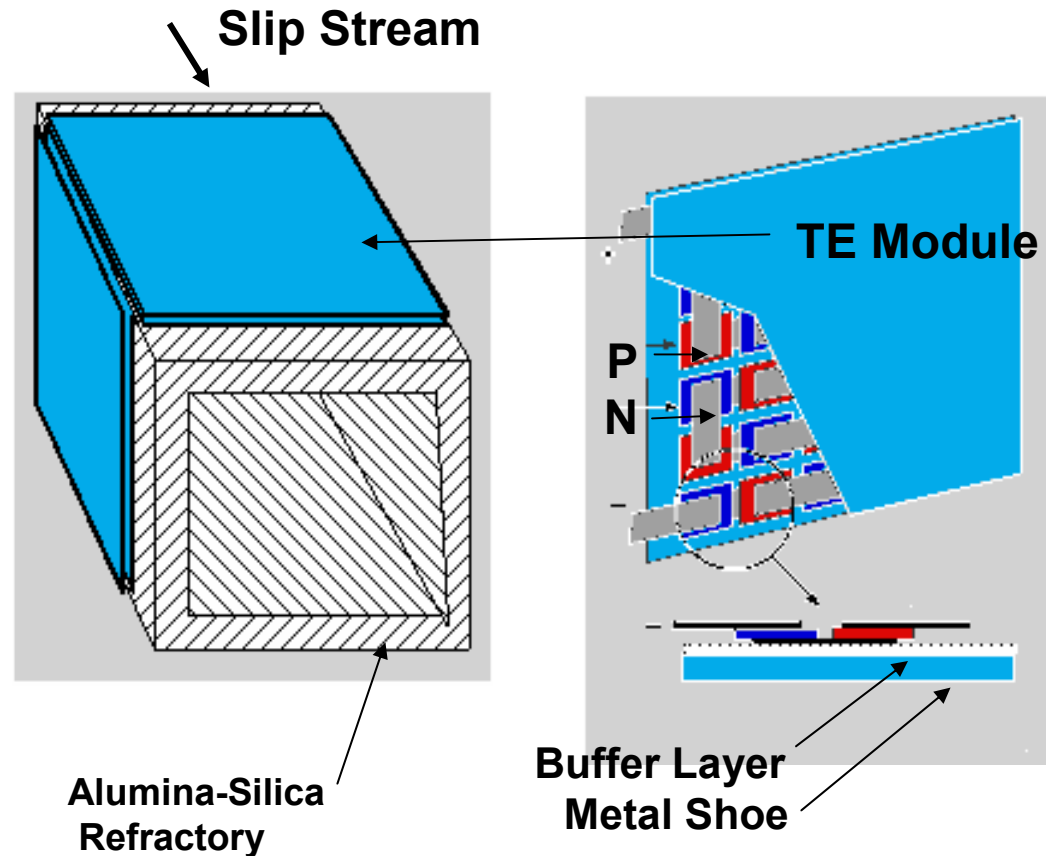
Sample No.	# Layers	S($\mu\text{V}/\text{K}$)	$\sigma(\Omega.\text{cm})^{-1}$	Power factor
1Q-S/FS	186	235	116	0.002
1S-S/FS	200	110	110	0.0011
1T-S/FS	300	127	127	0.0012

TEG System Components

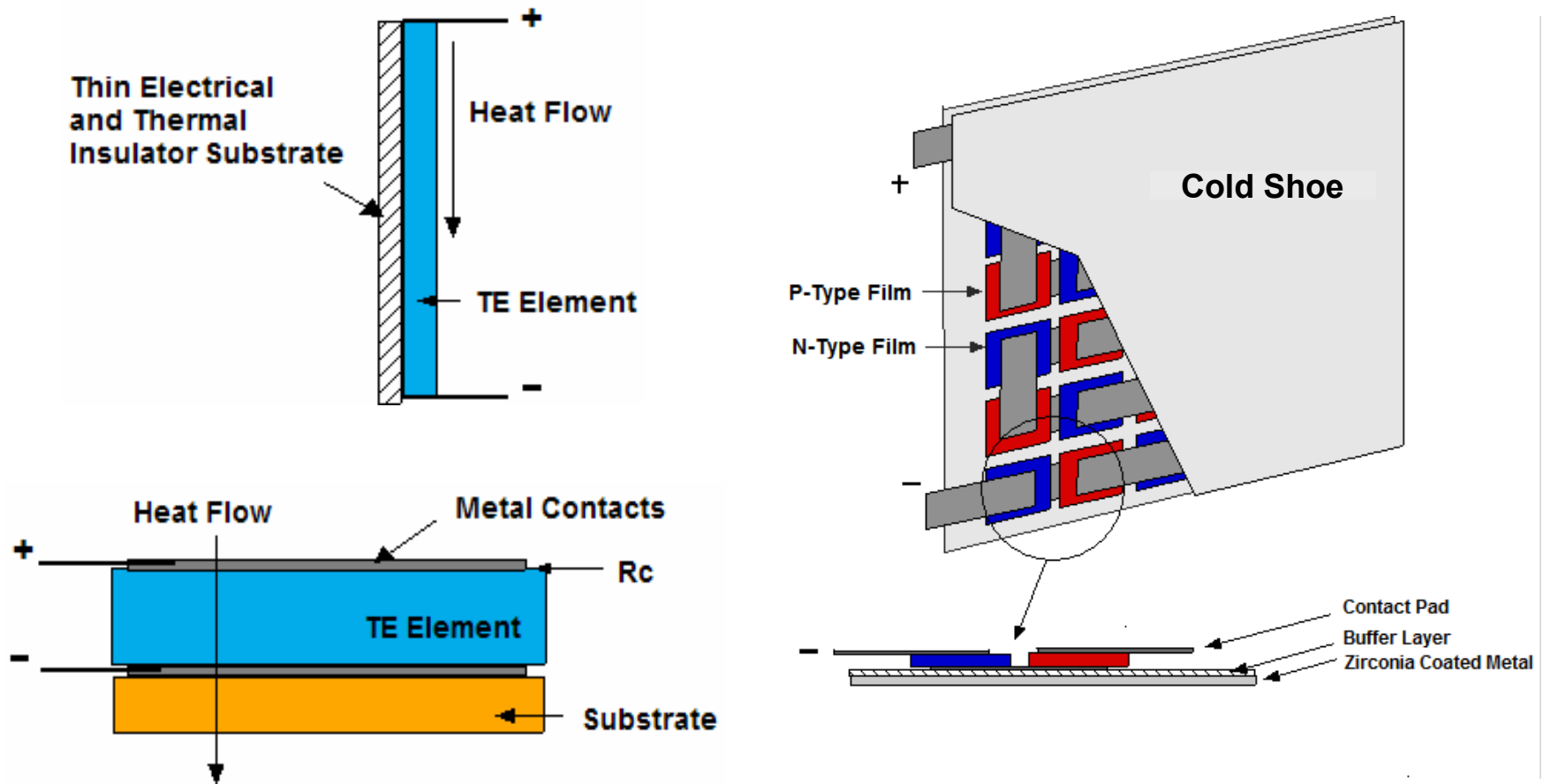
- ❑ **Heat Exchanger Coupled to Waste Heat Source**
- ❑ **TEG Module**
- ❑ **Cold Side Heat Exchanger**

Preliminary Concept for Waste Heat Conversion Test Bed

- **Assumptions:**
 - Utilize Slip Stream from Oxy-Furnace-Gas at 2700°F
 - Temperature at Hot Shoe 1160°F (900°K) with 1 cm Firebrick
 - Using Water Cooling Cold Shoe at 73°F (300°K)
- **Heat Flow into TE Modules:**
1.3 W/cm²
- **Four 1 meter x 10 cm TE Converters:**
 - 520 Watts @ 10% Efficiency
 - 1040 Watts @ 20% Efficiency



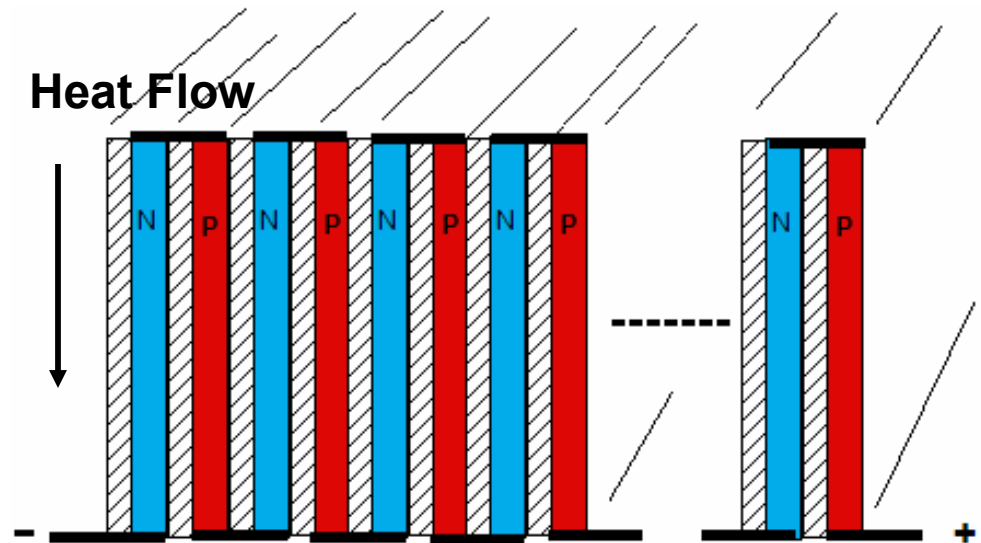
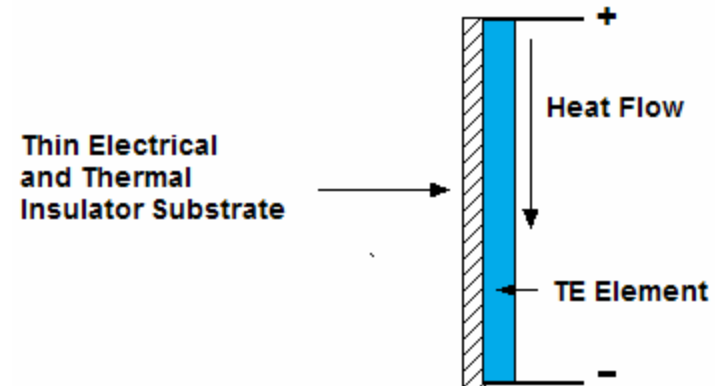
Configuration for Thin Films in Modules



Thin Film Modules – Parallel Flow

Key Issues

- ❑ Thin Film Deposition on Thin Insulating Substrates
 - Thickness (10s of microns)
 - Stress in Films
 - **TE Properties of Films**
- ❑ Substrates
 - **Thickness < 1 mil**
 - **Low Thermal and Electrical Conductivity**
- ❑ Contact Technology



Thin Film Modules – Normal Flow

Key Issues

□ Thin Film Deposition

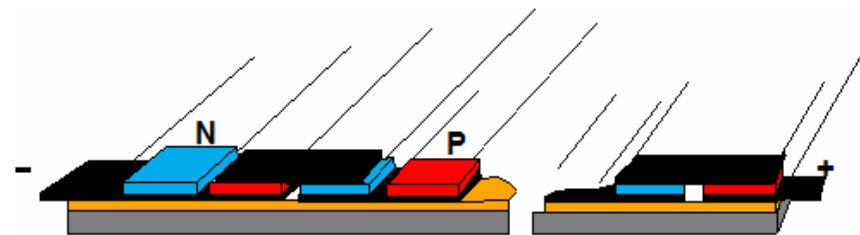
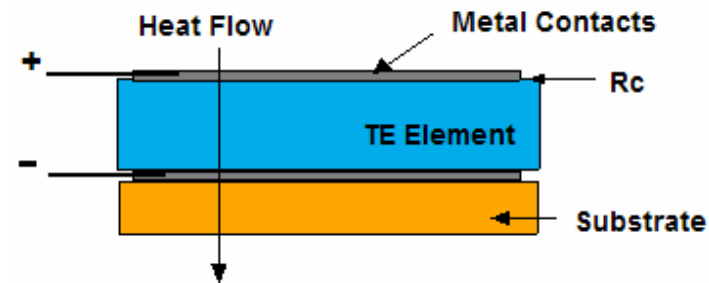
- Thickness (Need 100 microns)
- Stress in Films
- TE Properties of Films

□ Substrates

- Good Thermal Conductivity
- Electrically Insulating
- Can Be Coated Metal Sheet

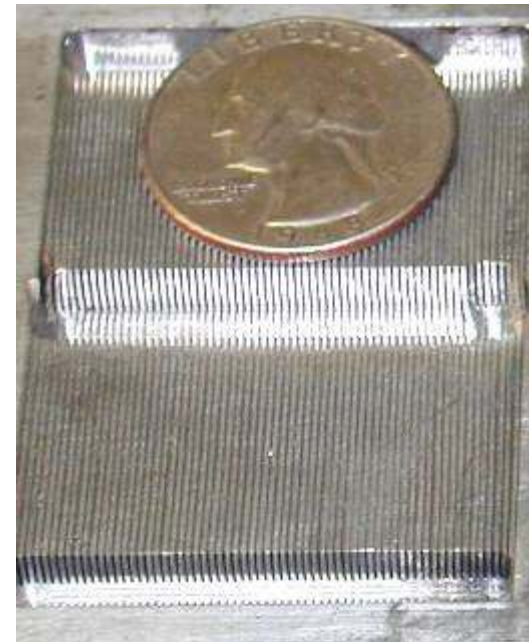
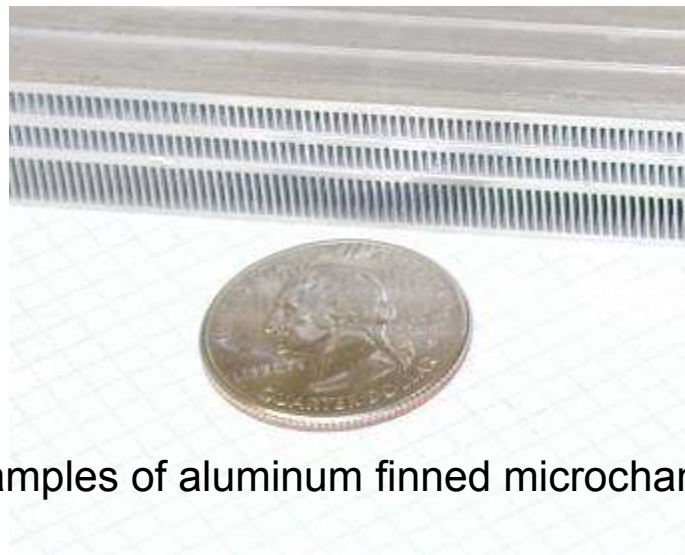
□ Contact Technology

- Contact Resistance Must Be Very Low



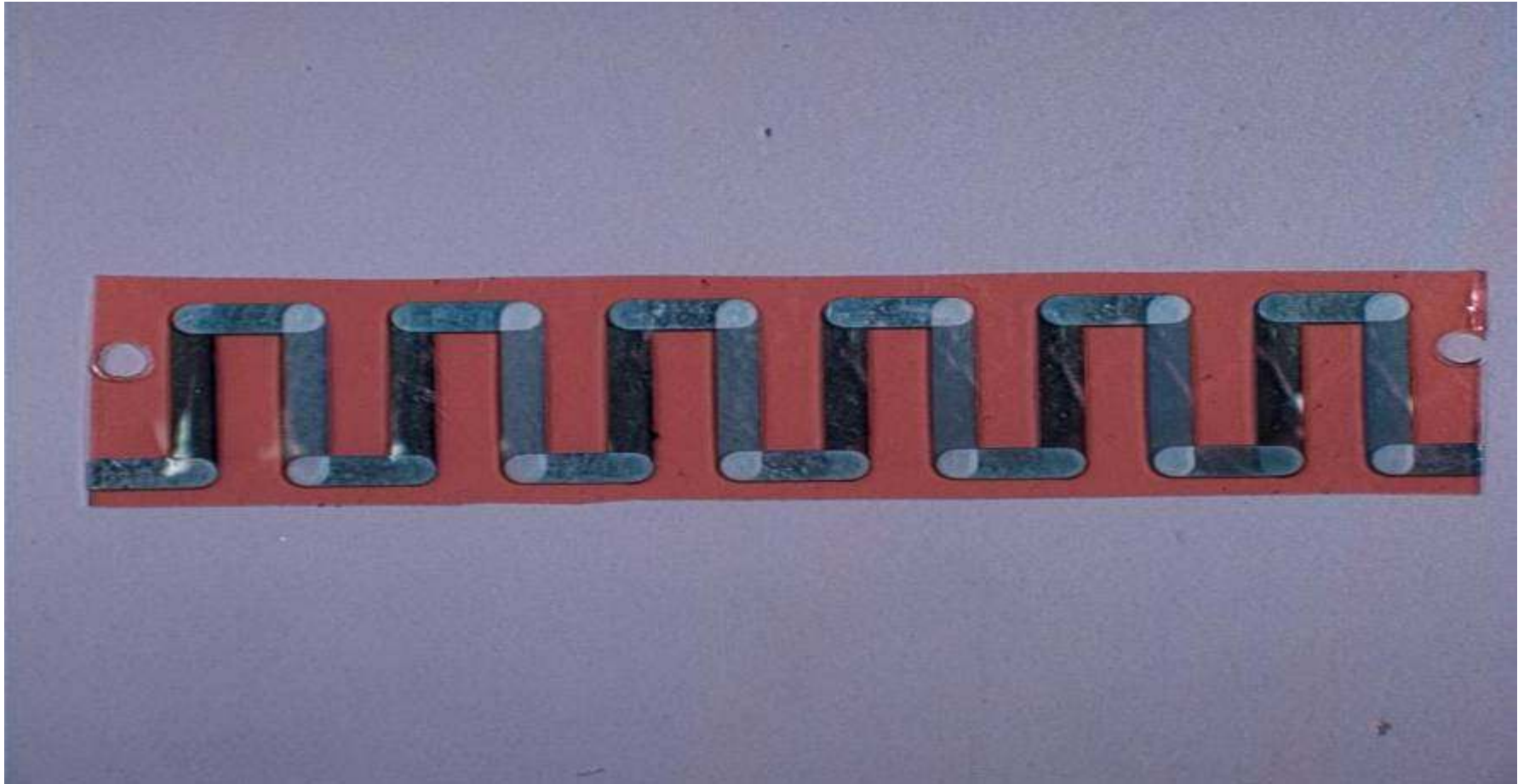
The Path Forward to Low Cost Thin Film TEG with High Conversion Efficiency

- Low cost deposition of multilayer TE thin film materials *on non-Si substrates*
- New TE materials – thin films and nanocomposites
- Integration into TEG module
 - Parallel or cross plane geometry
 - Electrical contacts
 - Efficient heat exchangers (cold/hot side)



Examples of aluminum finned microchannel heat exchanger structures

Thin film Bi_2Te_3 p-n TE module on polyimide web substrate



Status of TE Thin Films

- Multilayers perform much better than single layers
- Substrate thermal conductivity critical
 - Models show that high ZT and conversion efficiencies cannot be achieved using Si substrates (even for very high ZT ~ 4)
 - Disordered microstructure important for low thermal conductivity
- Low cost high efficiency thin film TE structures can be best realized on non-crystalline substrates
- All development work now focused on non-crystalline substrates
 - Presently BC system offer promise, but needs further work
 - New thin film materials being evaluated
 - Efficiencies > 15 % can be realized with ZT ~2

Other Nanostructured TE Materials Systems

- ▶ Bulk Bi_2Te_3 : $ZT \sim 1$
 - Marlowe
- ▶ $\text{Bi}_2\text{Te}_3/\text{Sb}_2\text{Te}_3$ quantum well: $ZT \sim 2$, maybe 2.5
 - MBE
 - RTI
- ▶ $\text{PbTe}/\text{PbSnTe}$ quantum dots: $ZT > 2$
 - MIT Lincoln Laboratory
 - MBE
- ▶ Nanoparticle Ag in oxide

**CLICK TO RETURN
TO LIST OF
PAPERS AND
PRESENTATIONS**